



IFW

PATENT
8051-1036

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Shinichi SUMIDA et al.

Conf. 8479

Application No. 10/563,557

Filed January 5, 2006

FLUORINE-CONTAINING CYCLIC COMPOUND,
FLUORINE-CONTAINING POLYMERIZABLE MONOMER,
FLUORINE-CONTAINING POLYMER, AND RESIST
MATERIAL AND PATTERNING PROCESS

INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

May 11, 2006

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, the accompanying document, a copy of which is attached to this statement, is made of record on the enclosed sheet.

A concise explanation of the relevance of this item is that this reference was discovered during any searches they or their client had made, or that it was considered in the preparation of the application.

Respectfully submitted,

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RJP/lk

Attorney Docket No.:
8051-1036

Application No.:
10/563,557

Applicant:
Shinichi SUMIDA et al.

Filing Date:
January 5, 2006

Group Art Unit:

[illegible][illegible]

	KODAMA et al., "Synthesis of Novel Fluoropolymer for 157 nm Photoresists by Cyclo-polymerization", Proceedings of SPIE, Vol. 4690, 2002, pp. 76-83.

EXAMINER:

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

* Abstract provided for the Examiner's convenience